

1. An infrared detecting device comprising a heat-separation-structure diaphragm made of a thermal insulating material through a cavity from a silicon substrate 1, an infrared detection section formed on said diaphragm, and a heat absorption area on said infrared detection section through an insulation layer, wherein an etching aperture for forming the cavity is formed in said heat absorption area.

3. An infrared detecting device according to claim 2, wherein said plurality of etching apertures are formed in said heat absorption area at equal intervals.

5. An infrared detecting device according to claim 1, wherein said cavity is mainly formed through anisotropic etching.

6. An infrared detecting device according to any one of claims 1 to 5, wherein said infrared detecting device is a thermopile type.